

**IN THE CLAIMS:**

1. (Currently Amended): A transflective liquid crystal display device, comprising:

a substrate having a reflective portion and a transmissive portion;

a gate line on the substrate;

a data line crossing the gate line and defining a pixel region;

a thin film transistor connected to the gate line and the data line;

a plurality of uneven patterns consisting of a first organic material layer ~~alternating with uncovered portions of the substrate~~ within the reflective portion ~~excluding a peripheral portion of the pixel region~~, the uneven patterns partially covering the substrate ~~including a first organic material layer~~;

a second organic material layer on the first organic material layer, the second organic material layer having an open portion at the transmissive portion; and

a reflective layer on the second organic material layer having a transmissive hole at the open portion.

2. (Original): The device according to claim 1, wherein the first and second organic material layers are formed from a photosensitive material.

3. (Original): The device according to claim 2, wherein the photosensitive material comprises a photo-acrylic resin.

4. (Original): The device according to claim 1, further comprising an inorganic material layer covering the gate line, the data line, and the thin film transistor.
5. (Original): The device according to claim 4, wherein the inorganic material layer is formed of one of silicon nitride and silicon oxide.
6. (Original): The device according to claim 1, further comprising a pixel electrode on the reflective layer.
7. (Original): The device according to claim 1, wherein the thin film transistor comprises a gate electrode, an active layer, and source and drain electrodes.
8. (Original): The device according to claim 7, further comprising a gate pad connected to the gate line, a data pad connected to the data line, and a capacitor electrode overlapping the gate line.
9. (Original): The device according to claim 8, wherein the second organic material layer has a drain contact hole exposing the drain electrode, a capacitor contact hole exposing the capacitor electrode, a gate pad contact hole exposing the gate pad, and a data pad contact hole exposing the data pad.

10. (Withdrawn): A transfective liquid crystal display device, comprising:

first and second substrates facing into and spaced apart from each other, the first and second substrates having a reflective portion and a transmissive portion;

a gate line on an inner surface of the first substrate;

a data line crossing the gate line and defining a pixel region;

a thin film transistor connected to the gate line and the data line;

a first organic material layer in the pixel region, the first organic material layer having a plurality of uneven patterns at the reflective portion;

a second organic material layer on the first organic material layer, the second organic material layer having an open portion at the transmissive portion;

a reflective layer on the second organic material layer having a transmissive hole corresponding to the open portion;

a pixel electrode on the reflective layer;

a common electrode on an inner surface of the second substrate; and

a liquid crystal layer between the pixel electrode and the common electrode,

wherein the pixel electrode and the common electrode are separated by a first cell gap, and a second cell gap in the reflective portion, and the first cell gap is twice greater than the second cell gap in the transmissive portion.

11. (Withdrawn): The device according to claim 9, wherein the uneven patterns have a height equal to or less than the second cell gap.

12. (Currently Amended): A method of fabricating a transfective liquid crystal display device, comprising:

forming a gate line on a substrate having a reflective portion and a transmissive portion;

forming a data line crossing the gate line and defining a pixel region;

forming a thin film transistor connected to the gate line and the data line;

forming a first photosensitive organic material layer on the substrate;

forming a plurality of uneven patterns consisting of a first organic layer ~~alternating with uncovered portions of the substrate~~ within the reflective portion ~~excluding a peripheral portion of the pixel region, the uneven patterns including a first organic material layer~~ by performing an exposure and development process on the first photosensitive organic material layer, the uneven patterns partially covering the substrate;

forming a second photosensitive organic material layer on the substrate including the first organic material layer;

forming a second organic material layer having an open portion corresponding to the transmissive portion by performing an exposure and development process on the second photosensitive organic material layer; and

forming a reflective layer on the second photosensitive organic material layer having a transmissive hole corresponding to the open portion.

13. (Original): The method according to claim 12, wherein the first and second photosensitive material layers are formed of a photo-acrylic resin.

14. (Original): The method according to claim 12, further comprising forming an inorganic material layer covering the gate line, the data line, and the thin film transistor.

15. (Original): The method according to claim 14, wherein the inorganic material layer is formed of one of silicon nitride and silicon oxide.

16. (Original): The method according to claim 12, further comprising forming a pixel electrode on the reflective layer.

17. (Original): The method according to claim 12, further comprising forming a gate pad connected to the gate line, a data pad connected to the data line, and a capacitor electrode overlapping the gate line.

18. (Original): The method according to claim 17, wherein the second organic material layer comprises a drain contact hole exposing the drain electrode, a capacitor contact hole exposing the capacitor electrode, a gate pad contact hole exposing the gate pad, and a data pad contact hole exposing the data pad.

19. (Withdrawn): A method of fabricating a transflective liquid crystal display device, comprising:

- forming a gate line on a first substrate having a reflective portion and a transmissive portion;

- forming a data line crossing the gate line and defining a pixel region;

- forming a thin film transistor connected to the gate line and the data line;

- forming a first photosensitive organic material layer on the first substrate;

- forming a first organic material layer having a plurality of uneven patterns at the reflective portion by performing an exposure and development process on the first photosensitive organic material layer;

- forming a second photosensitive organic material layer on the first substrate having the first organic material layer;

- forming a second organic material layer having an open portion corresponding to the transmissive portion by performing an exposure and development process on the second photosensitive organic material layer;

- forming a reflective layer on the second organic material layer having a transmissive hole corresponding to the open portion;

- forming a pixel electrode on the reflective layer; forming a common electrode on a second substrate;

- attaching the first and second substrates to each other; and

- forming a liquid crystal layer between the pixel electrode and the common electrode,

wherein the pixel electrode and the common electrode are separated by a first cell gap in the transmissive portion and a second cell gap in the reflective portion, and the first cell gap is twice greater than the second cell gap.

20. (Withdrawn): The method according to claim 19, wherein the plurality of uneven patterns are formed to have a height equal to or less than the second cell gap.

21. (Withdrawn): A transflective liquid crystal display device, comprising:

- a substrate having a reflective portion and a transmissive portion;

- a gate line on the substrate;

- a data line crossing the gate line and defining a pixel region;

- a thin film transistor connected to the gate line and the data line;

- an inorganic material layer covering the entire surface of the substrate including the gate line, the data line, and the thin film transistor;

- a plurality of uneven patterns covering portions of the inorganic material layer within the reflective portion excluding a peripheral portion of the pixel region, the uneven patterns including a first organic material and alternating with uncovered portions of the inorganic material layer;

- a second organic material layer covering the first organic material layer and the uncovered portions of the inorganic material layer, the second organic material layer having an open portion at the transmissive portion; and

a reflective layer on the second organic material layer having a transmissive hole at the open portion.